

POSTER SESSIONS

Poster Session #1 - Tuesday 14 September (17:30 – 18:30)

INDU / Industrial hot topics

- INDU #096** A simple approach to transpose the deposition conditions in two different magnetron sputtering chambers: a case study of oxidation of sputter-deposited VN films
A. Garcia Wong, D. Pilloud, F. Capon, J.F. Pierson
Institut Jean Lamour, Nancy (FR)

NANO / Nanomaterials and nanostructured thin films

- NANO #018** PtCu@TiO₂ nanoparticles by low pressure plasma
E. Hays¹, L. Chavée¹, A. Achour¹, J.F. Colomer¹, L. Houssiau¹, S. Bruyère², A. Nominé², S. Lucas¹
¹ UNamur - Namur (BE)
² Univ. Lorraine, CNRS, IJL, Nancy (FR)
- ~~**NANO #082** Local plasma chemical etching of the silicon substrate surface by using of anodic alumina template
G. Gorokh¹, A. Lozovenko¹, A. Zakhlebaeva¹, M. Iji¹, A. Dinescu², R. Gavrila², A. Avram²
¹ Belarusian State University of Informatics and Radioelectronics, Minsk (BY)
² National Institute for Research and Development in Microtechnologies, Bucharest (RO)~~
- ~~**NANO #107** Nitrogenation of monolayer graphene films in N₂ and N₂-O₂ flowing afterglows: analysis of incorporation-limiting mechanisms
L. Stafford, G. Robert-Bigras, R. Martel
Univ. Montréal (CA)~~
- NANO #141** Transport of sulfur species in a microwave argon plasma column for functionalization of CVD-grown graphene films
C. Moderie^{1,2}, S. Blanchette¹, R. Martel^{3,2}, L. Stafford^{1,2}
¹ Département de Physique, Univ. Montréal (CA)
² Regroupement Québécois sur les Matériaux de Pointe (RQMP), Montréal (CA)
³ Département de Chimie, Univ. Montréal (CA)

PROC / Process control (including plasma diagnostics, plasma modelling)

- PROC #025** Adaptation of spark to atmospheric-pressure micro-plasma jets flow conditions
D. Gonçalves^{1,2}, J. Santos Sousa², S. Pasquiers², M. Lino Da Silva¹, L. Lemos Alves¹
¹ Instituto de Plasmas e Fusão Nuclear, Instituto Superior Técnico, Lisbon (PT)
² Univ. Paris-Saclay, CNRS, Laboratoire de Physique des Gaz et des Plasmas, Orsay (FR)
- PROC #081** Study of the influence of a substrate on the axis of the plasma discharge by Optical Emission Spectroscopy (OES)
L. Renoux
IRCER, Limoges (FR)
- PROC #084** Reaction of neutral species in homogeneous phase in molecular dynamics simulation of Ar/CH₄ plasma
G. Otakandza Kandjani, P. Brault, M. Mikikian
GREMI, UMR7344, CNRS -Univ. Orléans (FR)

- PROC #110** Mass spectrometric investigations in a Ar/CH₄ radio frequency low pressure discharge
E. Von Wahl, I. Ellien, T. Lecas, M. Mikikian
GREMI, CNRS / Univ. Orléans (FR)
- PROC #159** NO_x emissions intrinsic to water/gas hybrid DC arc plasma torch at different power levels and gas flow rates
R. Tomar^{2,3,4}, N. Kumar¹, V.S. Sikarwar⁵, A. Mašláni⁵, M. Jeremias⁵, M. Pohorely⁶
¹ *Univ. West Bohemia, Pilsen (CZ)*
² *Institute of Plasma Physics, Czech Academy of Sciences, Pilsen (CZ)*
³ *ORLEN Unipetrol Centre for Research and Education, Litvínov-Záluží (CZ)*
⁴ *Univ. Chemistry and Technology, Prague (CZ)*
⁵ *Institute of Plasma Physics, Czech Academy of Sciences, Prague (CZ)*
⁶ *Department of Power Engineering, Univ. Chemistry and Technology, Prague (CZ)*
- PROC #160** The role of energetic ions at the substrate in thin film plasma processing
A. Rawat, C. Linnane, T. Gilmore
Impedans Ltd, Dublin (IE)

Poster Session #2 – Wednesday 15 September (11:30 – 12:30)

DEPO / Plasma - deposited coatings for optical, electronical and other functionalities

- ~~DEPO #007~~ Deterioration mechanism of RF-sputtered ITO films on plastic substrates **canceled**
T. Fukuda, M. Taguchi, T. Shingu
Graduate School of Engineering, Univ. Osaka (JP)
- DEPO #019 Dual-functionality multilayer coating compatible with IML for automobile applications using reactive DC magnetron sputtering
H. Pizarro¹, M. Freitas¹, D. Dias¹, R. Carvalho¹, V. Paulo², J. Viana³, D. Dias⁴
¹ CeNTI – Centre for Nanotechnology and Smart Materials, Famalicao (PT)
² GLN, Leiria (PT)
³ Univ. Minho, Braga (PT)
⁴ PIEP - Innovation in Polymer Engineering, Guimarões (PT)
- DEPO #118 Effects of the operating parameters on aerosol-assisted atmospheric pressure plasma thin film deposition
R. Magnan, R. Clergereaux, P. Raynaud, N. Naudé
CNRS-LAPLACE, Toulouse (FR)
- ~~DEPO #136~~ How to allow adhesion of powder paint on insulating substrates? **canceled**
D. Debarnot¹, A. Colin²
¹ Institut des Molécules et Matériaux du Mans, Le Mans (FR)
² Centre de Transfert de Technologies du Mans, Le Mans (FR)
- ~~DEPO #154~~ Magnetron co-sputtered TiO₂/Ag/Cu antimicrobial coatings **canceled**
D. Gospodinova¹, I. Ivanova²
¹ TU-Sofia (BG)
² Sofia Univ. St. Kliment Ohridski, Sofia (BG)

GROM / Thin films growth and modelling

- GROM #030 High temperature oxidation resistance of metallic materials by PVD coatings: influence of the initial substrate roughness
A. Besnard¹, Q. Ostorero², G. Nkou Bouala¹, M.R. Ardigo-Besnard²
¹ Arts et Metiers Science and Technology – LaBoMaP, Paris (FR)
² Laboratoire Interdisciplinaire Carnot de Bourgogne (ICB), Dijon (FR)
- GROM #097 Microstructure and properties control in sputter-deposited Zr-Cu thin film metallic glasses
A. Borroto, S. Bruyère, D. Pilloud, D. Horwat, J.F. Pierson
Univ. Lorraine, CNRS, IJL, Nancy (FR)
- GROM #126 Epitaxial growth of (ZnO)_x(InN)_{1-x} films by magnetron sputtering: effects of surface polarity of ZnO substrates
R. Narishige, D. Yamashita, K. Kamataki, T. Okumura, K. Koga, M. Shiratani, N. Itagaki
Kyushu Univ., Fukuoka (JP)

HELI / Health and life science

- HELI #146 Investigation of the chemical stability of plasma-activated solutions
K. Sklias¹, K. Gazeli¹, T.H. Chung², A. Stancampiano³, S. Dozias³, C. Douat³, J.M. Pouvesle³, E. Robert³, L. Mir², J. Santos Sousa¹
¹ Univ. Paris-Saclay, CNRS, Laboratoire de Physique des Gaz et des Plasmas, Orsay (FR)
² Univ. Paris-Saclay, CNRS, Gustave Roussy, VTA, UMR 8203, Villejuif (FR)
³ GREMI, CNRS UMR 7344, Univ. Orléans (FR)

Poster Session #3 – Wednesday 15 September (14:00 – 15:00)

ENER / Renewable energies

- ENER #056** Optical performance of high temperature air-stable solar absorber coatings based on W/SiCH plasma multilayers
A. Diop¹, D. Ngoue^{1,2}, A. Carling-Plaza¹, A. Bousquet^{3,4}, S. Quoizola^{1,2}, T. Sauvage⁵, A. Goulet⁶, A. Soum-Glaude¹, É. Tomasella^{3,4}, L. Thomas^{1,2}
¹ PROMES-CNRS, Perpignan / Font-Romeu-Odeillo-Via (FR)
² Univ. Perpignan (FR)
³ ICCF, Institut de Chimie de Clermont-Ferrand (FR)
⁴ Univ. Clermont Auvergne, Aubière (FR)
⁵ CEMHTI (Conditions Extrêmes et Matériaux), Orléans (FR)
⁶ IMN, Institut des Matériaux Jean Rouxel, Nantes (FR)

LIQU / Plasma and liquids

- LIQU #004** Bi₂O₃ nano-sheets and nanotubes synthesized by discharges in liquid nitrogen
A.V. Nominé¹, M. Trad¹, T. Gries¹, C. Noel¹, J. Ghanbaja¹, A. Nominé^{1,2}, V. Milichko^{1,2}, T. Belmonte¹
¹ Univ. Lorraine, CNRS, IJL, Nancy (FR)
² ITMO Univ., St. Petersburg (RU)
- LIQU #032** ~~Efimov physics and few-body approximation in nuclear, atomic and molecular physics~~
 canceled
S. Pozdneev
FIAN, Moscow (RU)
- LIQU #033** ~~Resonances in electron scattering by molecules~~ **canceled**
S. Pozdneev
FIAN, Moscow (RU)
- LIQU #061** Synthesis of bismuth-based nanoparticles into an imidazolium ionic liquid by reactive magnetron sputtering
A. Bousquet, S. Ibrahim, J.M. Andanson, P. Bonnet
ICCF, Institut de Chimie de Clermont-Ferrand (FR)
- LIQU #128** Viscous droplet in a nonthermal plasma: microflow at plasma-liquid interface
T. Hoder, L. Potocnakova
Masaryk Univ., Brno (CZ)

NANO / Nanomaterials and nanostructured thin films

- NANO #024** Synthesis and characterization of plasmonic composites (Fe/La)/Au for enhanced optical properties
A.V. Nominé¹, T. Gries¹, C. Noel¹, J. Ghanbaja¹, A. Nominé^{1,2}, E. Gunina², V. Milichko^{1,2}, T. Belmonte¹
¹ Univ. Lorraine, CNRS, IJL, Nancy (FR)
² ITMO Univ., St. Petersburg (RU)
- NANO #057** Nanocomposite cermet coatings for CSP technologies deposited by RF reactive PVD assisted with microwave ECR sources
A. Diop¹, D. Ngoue^{1,2}, H. Glenat^{1,2}, A. Bousquet^{3,4}, S. Quoizola^{1,2}, T. Sauvage⁵, A. Goulet⁶, A. Soum-Glaude¹, É. Tomasella^{3,4}, L. Thomas^{1,2}
¹ PROMES-CNRS, Perpignan / Font-Romeu-Odeillo-Via (FR)
² Univ. Perpignan (FR)
³ ICCF, Institut de Chimie de Clermont-Ferrand (FR)
⁴ Univ. Clermont Auvergne, Aubière (FR)
⁵ CEMHTI (Conditions Extrêmes et Matériaux), Orléans (FR)
⁶ IMN, Institut des Matériaux Jean Rouxel, Nantes (FR)
- NANO #088** Charge gas and discharge parameters influence on kinetic and nucleation in RF Ar/C₂H₂ plasmas
G. Tetard¹, A. Michau¹, S. Prasanna¹, J. Mougenot¹, P. Brault², K. Hassouni¹
¹ LSPM, Villetaneuse (FR)
² GREMI, Orléans (FR)
- NANO #101** Investigation of the mechanisms involved in one-step nanocomposite thin films synthesis by direct pulsed liquid injection of a colloidal solution in a low-pressure plasma
S. Chouteau¹, M. Mitronika¹, M. Richard-Plouet¹, A. Goulet¹, A. Granier¹, L. Stafford²
¹ Univ. Nantes, CNRS, Institut des Matériaux Jean Rouxel, Nantes (FR)
² Département de Physique, Univ. Montréal, Québec (CA)
- NANO #102** Optimization of nanostructured TiAlBN coatings deposited by HiPIMS
A. Mendez Fernandez^{1,2,3}, J.A. Santiago¹, I. Fernández-Martínez¹, A. Wennberg¹, M.A. Monclús², J.M. Molina-Aldareguía²
¹ Nano4Energy SLNE, Madrid (ES)
² IMDEA Materials Institute, Getafe (ES)
³ Univ. Madrid (ES)

Poster Session #4 – Thursday 16 September (17:30 – 18:30)

NANO / Nanomaterials and nanostructured thin films

- NANO #105** – Enhanced resonance Raman scattering of spin-coated silver nanoparticles by treatment in a microwave argon plasma jet open to ambient air **canceled**
L. Stafford¹, J. Trahan¹, J. Profili¹, G. Robert-Bigras¹, M. Mitronika², A. Granier², M. Richard-Plouet²
¹Univ. Montréal (CA)
²Institut des Matériaux Jean Rouxel – Nantes (FR)

SOUR / Plasma sources and electrical discharges

- SOUR #064** Power balance in microwave microplasmas generated in capillary tubes
O. Leroy¹, F. Coquery², T. Minea¹, G.D. Stancu²
¹LPGP, Orsay (FR)
²EM2C, Gif Sur Yvette (FR)
- SOUR #140** The DC gas breakdown in tubes of arbitrary length
V. Lisovski, E. Bannikova, S. Dudin, R. Osmayev, V. Yegorenkov
V.N. Karazin Kharkiv National Univ., Kharkiv (UA)

SURF / Plasma - surface interactions

- SURF #047** – Atmospheric pressure plasma microfluidic chips wettability treatment **canceled**
A. Stolz¹, A. Audebert¹, C. Douat¹, S. Dozias¹, S. Roman², T. Tillocher¹
¹GREMI – CNRS UMR 7344, Univ. Orléans (FR)
²ISTO – BRGM CNRS UMR 7327, Univ. Orléans (FR)
- SURF #080** Cryo-ALE of Si based on SF₆ physisorption
J. Nos¹, G. Antoun¹, T. Tillocher¹, P. Lefauchaux¹, J. Faguet², K. Maekawa³, R. Dussart¹
¹GREMI, CNRS, Univ. Orléans (FR)
²Tokyo Electron America, Austin (US)
³TEL Technology Center, Albany (US)
- SURF #089** Plasma surface activation of CFRP substrate to enhance adhesion of PVD/PECVD coatings
N. Ranger¹, C. Jaoul², P. Tristant², T. Maerten¹, S. Belveze¹, S. Guimond³, M. Cavarroc⁴
¹OERLIKON Balzers France, Limoges (FR)
²IRCER, UMR CNRS 7315, Univ. Limoges (FR)
³OERLIKON Balzers Liechtenstein, Balzers (LI)
⁴SAFRAN TECH, Châteaufort (FR)
- SURF #109** Contributions of grain boundaries in plasma-modified graphene
P. Vinchon, X. Glad, G. Robert Bigras, R. Martel, L. Stafford
Univ. Montréal (CA)
- SURF #137** – Atmospheric pressure plasma for surface engineering applications **canceled**
A. Bishop¹, Z. Huang¹, C. Giusca¹, A. Bennett², M. Castelli^{2,3,4}, J. Nicholls¹
¹Cranfield Univ. (UK)
²Cranfield Plasma Solutions (UK)
³The Manufacturing Technology Centre (MTC), Coventry (UK)
⁴Univ. College Dublin (IE)

SURF #142 ~~Effect of plasma sources on the surface modification of carbon reinforced epoxy by atmospheric pressure plasma treatment~~ **canceled**
L. Frumosu, A. Bennett, Z. Huang, J. Nicholls
Cranfield Univ. (UK)

TRIB / Plasma - deposited protective and tribological coatings

TRIB #065 Structure, stress and mechanical properties of Mo-Al-N sputter-deposited thin films: role of point defects
G. Abadias¹, F. Angay¹, D. Eyidi¹, L. Löfler², D. Holec², P. Djemia³, F. Tétard³
¹ Institut Pprime - CNRS – Univ. Poitiers, Chasseneuil-Futuroscope (FR)
² Department of Materials Science, Univ. Leoben (AT)
³ LSPM, Univ. Sorbonne Paris Nord, Villetaneuse (FR)

TRIB #072 ~~Enhanced tribomechanical performance of metal doped DLC coatings deposited by HiPIMS with positive pulse technology~~ **canceled**
J. Santiago¹, I. Fernandez¹, A. Wennberg¹, J.L. Endrino¹, M. Panizo², J. Molina³, M. Monclus³
¹ Nano4Energy, Madrid (ES)
² Univ. Politécnica de Madrid (ES)
³ IMDEA Materiales, Madrid (ES)

TRIB #122 Resonant nuclear reaction analysis investigation of nitrogen and oxygen diffusion processes involved in plasma assisted multi-interstitials surface hardening of Ti6Al4V alloy
L. Pichon¹, M. Drouet¹, P. Berger², Y. Vallet¹, R. Genin¹
¹ Institut P' - CNRS UPR3346 – Univ. Poitiers (FR)
² LEEL, UMR 3685, CEA/CNRS NIMBE, CEA Saclay, Paris (FR)

PROC / Process control (including plasma diagnostics, plasma modelling)

PROC #081 Study of the influence of a substrate on the axis of the plasma discharge by Optical Emission Spectroscopy (OES)
L. Renoux
IRCER, Limoges (FR)

Poster Session #5 – Friday 17 September (11:30 – 12:30)

DEPO / Plasma - deposited coatings for optical, electronical and other functionalities

- DEPO #077** Direct observation of twinning domains in copper iodide thin film synthesized by magnetron sputtering of Cu thin layers at low temperature and iodine vapor
O. Madkhali^{1,2}, J. Ghanbaja¹, A. Redjaimia¹, F. Alnjiman¹, A.E. Giba^{1,3}, M. Jullien¹, J.F. Pierson¹
¹ Institut Jean Lamour (UMR CNRS 7198), Univ. Lorraine, Nancy (FR)
² Department of Physics at College of Science, Univ. Jazan (SA)
³ National Institute of Laser Enhanced Sciences, Cairo Univ., Giza (EG)
- DEPO #119** EELS study of SmNiO₃ thin films deposited by magnetron sputtering with a soft air atmosphere post-annealing
Z. Fernandez, S. Bruyère, D. Kharkhan, D. Pilloud, S. Barrat, F. Capon
Univ. Lorraine, CNRS, IJL, Nancy (FR)
- DEPO #124** PE-CVD with organometallic precursors: contribution of aerosol assisted processes
R. Clergereaux¹, C. Simonnet^{1,2}, E. Loranger², G. Carnide^{3,1}, L. Cacot^{1,2}, D. Roubert^{3,4}, D. Zargarian⁴, L. Stafford², J.C. Hierso⁵, M.L. Kahn³
¹ Laplace – Univ. Toulouse (FR)
² Dpt de Physique – Univ. Montréal (CA)
³ LCC – CNRS, Univ. Toulouse (FR)
⁴ Dpt de Chimie – Univ. Montréal (CA)
⁵ ICMUB – Univ. Bourgogne (FR)
- DEPO #125** Plasma polymer for enhancing adhesion bonds of metal/elastomer assembly
F. Poncin-Epaillard, M. Ji, L. Benyahia
IMMM, Le Mans (FR)
- ~~**DEPO #155** Fabrication and characterization of magnetron co-sputtered TiO₂/SiO₂/Ag coatings inhibiting bacterial adhesion and biofilm formation~~ **canceled**
T. Vladkova¹, I. Ivanova², F. Mergulhae³
¹ UCTM, Sofia (BG)
² Sofia Univ. "St. Kl. Ohridski", Sofia (BG)
³ Univ. Porto (PT)

GROM / Thin films growth and modelling

- GROM #063** Multi-scale modelling of sputtered deposited TiN, ZrN, HfN and TiAlN thin films at oblique angle incidence
C. Mastail, R. Mareus, F. Nita, A. Michel, G. Abadias
Institut Pprime, UPR 3346, CNRS-Univ. Poitiers-ENSMA, Poitiers (FR)
- GROM #087** Optimization of the anti-reflective coating (SiC_xN_yH) / Silicon interface to improve silicon photovoltaic cell performance
H. Beji¹, C. Robert-Goumet², E. Tomasella³, G. Monier², A. Bousquet³
¹ Chemistry and physics of materials - IP-ICCF Clermont-Ferrand (FR)
² Physics of materials - IP- Clermont-Ferrand (FR)
³ Chemistry of materials - ICCF- Clermont-Ferrand (FR)
- GROM #132** Effect of the deposition rate on competitive growth between amorphous and crystalline phases in sputtered Zr-Cr thin films
Q. Liebgott^{1,2}, A. Borroto¹, Z. Fernandez-Gutierrez¹, S. Bruyère¹, D. Horwat¹
¹ Univ. Lorraine, CNRS, IJL, Nancy (FR)
² Chair of Functional Materials, Saarland Univ., Saarbrücken (DE)

HELI / Health and life science

~~**HELI #121** — The application of Cold Atmospheric Plasma (CAP) in medicine
M. Rezaei
Shahid Beheshti Univ., Tehran (IR)~~

canceled